

1 Introduction

We have designed and realized a new electric field detector (EFD) to be installed on board scientific space missions suitable to investigate electromagnetic phenomena in ionosphere. The instrument measures electric field in a large bandwidth from quasi-DC up to about 5 MHz. The resolution of the proposed instrument in the ULF band is better than $1\mu V/m$ with a dynamic range of 120 dB. The sensitivities in the other bands (*ELF*, *VLF* and *HF*) are better than $300 \frac{nV}{\sqrt{Hz}}$. Considering the boom lengths, it can be expressed in terms of electric field and becomes of the order of $50 \frac{nV}{\sqrt{Hz m}}$. We present the description of the instrument electronics and the results of the preliminary tests performed on the EFD prototype in laboratory. The general EFD block diagram is shown in fig. 1.

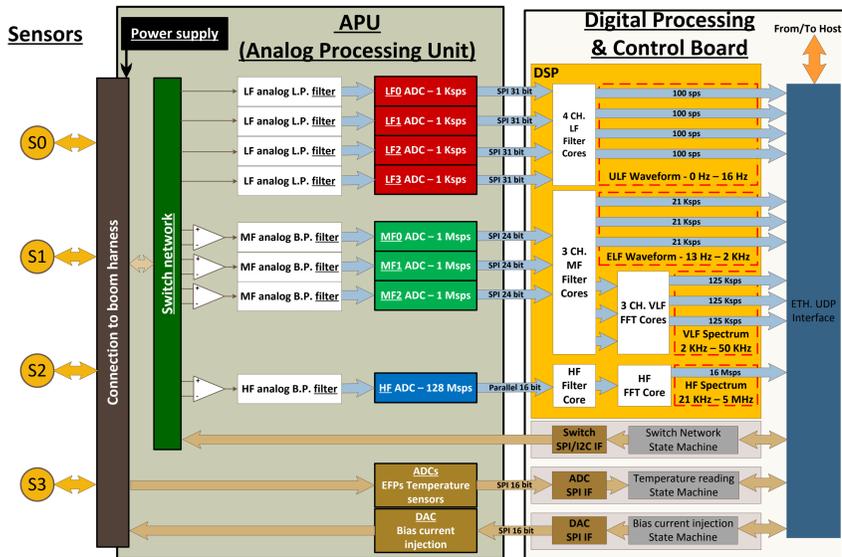


Figure 1: EFD block diagram.

The instrument consists of four independent identical sensors (from *S0* through *S3*) followed by two boards for signal conditioning, digital conversion and processing. The sensors are installed at the tips of four booms (about four meters long) deployed from a 3-axes stabilized spacecraft. The Analog Processing Unit (*APU*) performs a fully flexible selection of the sensors and provides a preliminary filtering and band subdivision. The Digital Processing & Control Board carries out a decimation process for *ULF* and *ELF* bands, the Fast Fourier Transform for *VLF* and *HF* bands and transmission control of data & commands to/from host PC and *APU*.

2 Description

Description of the sensors

The electric field will be derived by dividing the potential difference measured across a pairs of sensors to their mutual distance.

Each sensor consists of a spherical electrode exposed to the ionospheric plasma connected to a very high input impedance voltage follower. The block diagram of one EFD sensor is shown in fig. 2 along with photographs of the prototype.

The contact impedance (dV/dI) between electrode and plasma reaches a minimum when the electrode is biased at the plasma potential (assumed equal to zero) whereas significantly increases when the electrode acquires a negative potential. Usually a floating electrode in plasma acquires a negative potential (floating potential), thus the EFD has to use a current generator in order to bias itself close to the plasma potential to minimize the contact impedance and improve the measurement accuracy.

The electronics is shielded from the external current collecting electrode through an inner conductive shell which is bootstrapped at sensor potential in order to minimize the effect of the stray capacitance. The short stubs placed at the opposite sides of the boom axis (aligned with the boom axis) aim at reducing the asymmetry introduced by the presence of the boom and are bootstrapped at the same potential of the sensor. The low-pass filter visible in fig. 2 is used to optimize the frequency response of the amplifier.

Description of the Analog Processing Unit (APU) and Digital Processing & Control Board (DPCB)

The architecture of the *APU* is depicted in fig. 1. Its main purpose is subdivide the signals coming from the sensors into three bands: *LF* from 0 to 16 Hz; *MF* from 13 Hz to 50 kHz and *HF* from 21 kHz to 5 MHz. We have four single channels for the *LF* band, the output signals are digitized with 31 bit *ADC* at 1 ksp/s data rate.

Name	APU Freq. range	Name	DPCB Freq. range	OUTPUT
LF	0 - 16 Hz	ULF	0 - 16 Hz	Waveform
MF	13 Hz - 50 kHz	ELF	13 Hz - 2 kHz	Waveform
		VLF	1 kHz - 50 kHz	Spectrum
HF	21 kHz - 5 MHz	HF	21 kHz - 5 MHz	Spectrum

Table 1: Definition of the frequencies bands.

mand the suitable bias current for the sensors.

The *DPCB*, described in fig. 1, provides a further digital elaboration on the *APU* output data (*DSP* block) in order to: i) improve the filter roll-off, ii) separate the *MF* bands into *ELF* and *VLF* bands, iii) built the *FFT* spectra of the *VLF* and *HF* bands. See table 1 for details. Moreover the *DPCB* implements the digital stimuli for the bias current and the ethernet protocols for connection and data exchange to a host computer.

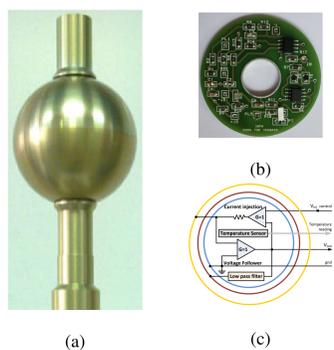


Figure 2: EFD probe prototype. Photograph of sensor (a) and board (b). (c) Block diagram: orange line represents the sensor current collector, brown is the inner bootstrapped shield and blue is the grounded shield.

For the *MF* band there are three independent channels, the output signal are sampled with 24 bit *ADCs* at 1 *Msp/s* data rate. There is a unique channel for the *HF* band whose signal output is sampled with 16 bit *ADCs* at 128 *Msp/s* data rate. The input of the *MF* and *HF* channels can be connected to the sensor through a switch matrix allowing a complete flexible reconfigurability. The *APU* contains the *DAC* needed to com-

3 Test results

Due to the high input impedance of the sensors, a Faraday cage has been used to shield the sensors in order to protect them from external electromagnetic noise.

All measurements were carried out taking the signals from the outputs of each analog processing chain (just at the *ADCs* inputs) prior digitization.

We have performed the tests varying two parameters: i) the equivalent electric circuit which represents the *plasma coupling impedance* and ii) the bias current.

Values of the plasma impedance are estimated for three different combinations of plasma densities and temperatures which can be considered as the extremes and medium values expected along the *CSES* orbit. The plasma coupling parameters adopted for measurements are shown in table 2. These represent the extreme and typical values of possible plasma conditions encountered along a ionospheric orbit [2].

Electronic Noise The *Electronic noise* measurements are given in terms of *Voltage Noise Spectral Density* vs frequency and determine the EFD *sensitivities* in each band. For the *LF* band the noise is given in terms of V_{rms} according to: $V_{rms} = \sqrt{\int_0^{f_{high}} (V_D(f))^2 df}$ (eq. 1) where $V_D(f)$ is the voltage noise density expressed in $\frac{V}{\sqrt{Hz}}$ and f_{high} is the high cutoff frequency of the *LF* band. The resulting V_{rms} represents the EFD resolution in that band.

Dynamic Range We define the *Dynamic range* as $DR = 20 \cdot \log \frac{V_{RMSMAX}}{V_{RMSMIN}}$, where V_{RMSMAX} is the maximum V_{RMS} obtainable at the output, in absence of distortions or saturations, whereas V_{RMSMIN} is the noise level.

3.1 Noise test results

Fig. 3 shows the voltage noise spectral densities for the *LF*, *MF* and *HF* channels measured in various plasma conditions. Panel (a) and (b) show the *LF* noise density for C_2 and C_3 plasma conditions, respectively. Panel (c) gives the noise measured for *MF* band under C_2 plasma condition. Panel (d) provides the noise measured for *HF* band for C_2 plasma condition.

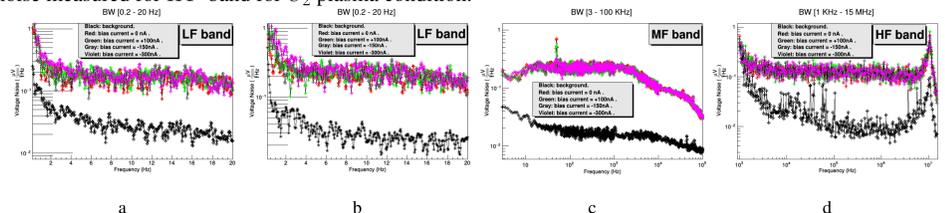


Figure 3: Voltage noise spectral density vs frequency: (a) *LF* channel with C_2 plasma condition; (b) *LF* channel for C_3 plasma condition; (c) *MF* channel for C_2 plasma condition; (d) *HF* channel for C_2 plasma condition. All tests have been obtained for several values of the *bias current*. The black traces represent the noise due to the measurement instrumentation determined while the EFD electronics is powered off.

Table 3 shows the results of the calculated V_{rms} noise for various bias currents obtained with different plasma conditions applying eq. (1).

The results show that the noise spectral density is almost independent from the values of the injected bias current. On the basis of the *CSES* configuration, which foresees boom lengths of about four meters (about eight meters tip to tip), the electric field resolution is better than $1\mu V/m$.

3.2 Dynamic range test results

We obtain the values shown in table 4.

Band	Analog chain	ADC
LF	120 dB	124 dB
ELF	139 dB	105 dB
VLF	115 dB	105 dB
HF	87 dB	78 dB

Table 4: EFD: Dynamic range for each band.

3.3 Transfer function test results

Fig. 4 shows the analog transfer functions for *LF* (panel (a)), *MF* (panel (b)) and *HF* (panel (c)). Note that the slight decay of the transfer function amplitudes within the bandwidth of the *MF* and *HF* filters, starting at about 20 kHz, are due to the low-pass pole associated to the plasma coupling equivalent electric circuit used to simulate the various plasma conditions.

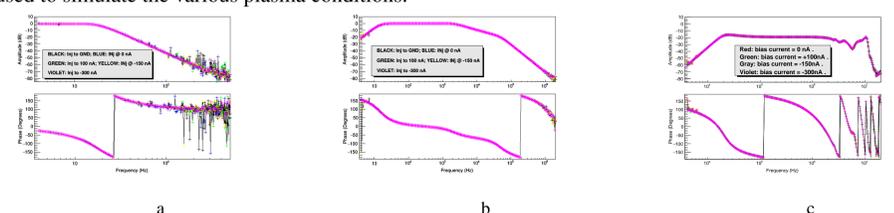


Figure 4: EFD transfer functions measured for the *LF* (panel a), *MF* (panel b) and *HF* (panel c) bands applying at the input the equivalent electric circuit simulating C_2 plasma condition.

Acknowledgments

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